

ABSTRACT OF THE DISCLOSURE

The present invention provides a very-reliable charging control technique without a process requiring experience and skill to suppress charging which occurs 5 in the surface of a sample containing an insulating material, and provides an apparatus for a charged particle beam, of generally excellent analyzing and sample fabricating efficiency. In an apparatus for a charged particle beam having: a charged particle 10 source; a charged particle optical system for focusing and deflecting a charged particle beam emitted from the charged particle source; a detector for detecting secondary particles emitted from a sample irradiated with the charged particle beam; and a sample holder on 15 which the sample is mounted, the apparatus has an electrode for preventing charging which is provided so as to be movable with respect to the surface of the sample holder, and a controller for the electrode for preventing charging, which controls a voltage to be 20 applied to the electrode for preventing charging and the movement. A control for preventing the charging is performed by generating an induced current or a current between an area irradiated with the charged particle beam in the sample and the electrode for preventing 25 charging.